

WHAT IS CLAIMED IS:

1. A method for operating an optical disk memory comprising the steps
of:
introducing an optical disk having a surface protected by a protective
5 film comprising a diamond-like carbon having a thickness of 500Å or less;
irradiating a semiconductor laser light onto said optical disk through
said diamond-like carbon;
wherein the number of pin-holes in said diamond-like carbon is
30/mm² or less.

10 2. A method according to claim 1 wherein said protective film is formed
on the surface of said optical disk without heating.

3. A method according to claim 1 wherein said optical disk memory is
a compact disk.

15 4. A method according to claim 1 wherein film quality of said diamond-
like carbon is measured in accordance with Raman spectroscopy.

5. A method according to claim 1 wherein the thickness of said
diamond-like carbon is 50Å or more.

6. A method according to claim 1 wherein said semiconductor laser light
has a wavelength of 700 to 800 nm.

20 7. A method according to claim 1 wherein said semiconductor laser light
is a visible light.

Sub B3

8. A method for operating an optical disk memory comprising the steps of:
introducing an optical disk having a surface protected by a protective film comprising a diamond-like carbon having a thickness of 500Å or less;
5 irradiating a semiconductor laser light onto said optical disk through said diamond-like carbon;
wherein the number of pin-holes in said diamond-like carbon is 30/mm² or less;
wherein said diamond-like carbon contains at least one of element
10 selected from the group consisting of Si, B, N, P and F.
9. A method according to claim 8 wherein said protective film is formed on the surface of said optical disk without heating.
10. A method according to claim 8 wherein said optical disk memory is
15 a compact disk.
11. A method according to claim 8 wherein film quality of said diamond-like carbon is measured in accordance with Raman spectroscopy.
12. A method according to claim 8 wherein the thickness of said diamond-like carbon is 50Å or more.
- 20 13. A method according to claim 8 wherein said semiconductor laser light has a wavelength of 700 to 800 nm.
14. A method according to claim 8 wherein said semiconductor laser light is a visible light

15. A method for operating an optical disk memory comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a diamond-like carbon having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said substrate through said diamond-like carbon;

wherein the number of pin-holes in said diamond-like carbon is 30/mm² or less.

16. A method according to claim 15 wherein said protective film is formed on the surface of said substrate without heating.

17. A method according to claim 15 wherein said optical disk memory is a compact disk.

18. A method according to claim 15 wherein film quality of said diamond-like carbon is measured in accordance with Raman spectroscopy.

19. A method according to claim 15 wherein the thickness of said diamond-like carbon is 50Å or more.

20. A method according to claim 15 wherein said semiconductor laser light has a wavelength of 700 to 800 nm.

21. A method according to claim 15 wherein said semiconductor laser light is a visible light.

22. A method for operating an optical disk memory comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a diamond-like carbon having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said substrate through
5 said diamond-like carbon;

wherein the number of pin-holes in said diamond-like carbon is 30/mm² or less;

wherein said diamond-like carbon contains at least one of element selected from the group consisting of Si, B, N, P and F.

10 23. A method according to claim 22 wherein said protective film is formed on the surface of said substrate without heating.

Sub B6
24. A method according to claim 22 wherein said optical disk memory is a compact disk.

15 25. A method according to claim 22 wherein film quality of said diamond-like carbon is measured in accordance with Raman spectroscopy.

26. A method according to claim 22 wherein the thickness of said diamond-like carbon is 50Å or more.

27. A method according to claim 22 wherein said semiconductor laser light has a wavelength of 700 to 800 nm.

20 28. A method according to claim 22 wherein said semiconductor laser light is a visible light.

29. A method for operating an optical disk memory comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said optical disk through said hard-carbon coating;

5 wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less.

30. A method according to claim 29 wherein said protective film is formed on the surface of said optical disk without heating.

10 31. A method according to claim 29 wherein said optical disk memory is a compact disk.

32. A method according to claim 29 wherein film quality of said hard-carbon coating is measured in accordance with Raman spectroscopy.

33. A method according to claim 29 wherein the thickness of said hard-carbon coating is 50Å or more.

15 34. A method according to claim 29 wherein said semiconductor laser light has a wavelength of 700 to 800 nm.

35. A method according to claim 29 wherein said semiconductor laser light is a visible light.

20 36. A method for operating an optical disk memory comprising the steps of:
introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less;

5 wherein said hard-carbon coating contains at least one of element selected from the group consisting of Si, B, N, P and F.

37. A method according to claim 36 wherein said protective film is formed on the surface of said optical disk without heating.

10 38. A method according to claim 36 wherein said optical disk memory is a compact disk.

39. A method according to claim 36 wherein film quality of said hard-carbon coating is measured in accordance with Raman spectroscopy.

40. A method according to claim 36 wherein the thickness of said hard-carbon coating is 50Å or more.

15 41. A method according to claim 36 wherein said semiconductor laser light has a wavelength of 700 to 800 nm.

42. A method according to claim 36 wherein said semiconductor laser light is a visible light.

20 43. A method for operating an optical disk memory comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said substrate through
said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is
30/mm² or less

5 44. A method according to claim 43 wherein said protective film is
formed on the surface of said substrate without heating.

Sub B12 45. A method according to claim 43 wherein said optical disk memory
is a compact disk.

10 46. A method according to claim 43 wherein film quality of said hard-
carbon coating is measured in accordance with Raman spectroscopy.

47. A method according to claim 43 wherein the thickness of said hard-
carbon coating is 50Å or more.

Sub B13 48. A method according to claim 43 wherein said semiconductor laser
light has a wavelength of 700 to 800 nm.

15 49. A method according to claim 43 wherein said semiconductor laser
light is a visible light.

Sub B14 50. A method for operating an optical disk memory comprising the steps
of:

20 introducing a substrate made of an organic resin or an industrial
plastic material, said substrate having a surface protected by a protective film
comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said substrate through
said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less;

wherein said hard-carbon coating contains at least one of element selected from the group consisting of Si, B, N, P and F.

5 51. A method according to claim 50 wherein said protective film is formed on the surface of said substrate without heating.

52. A method according to claim 50 wherein said optical disk memory is a compact disk.

10 53. A method according to claim 50 wherein film quality of said hard-carbon coating is measured in accordance with Raman spectroscopy.

54. A method according to claim 50 wherein the thickness of said hard-carbon coating is 50Å or more.

15 55. A method according to claim 50 wherein said semiconductor laser light has a wavelength of 700 to 800 nm.

56. A method according to claim 50 wherein said semiconductor laser light is a visible light.

665160" T8E96E60

Add
C19

H1